

**Ben Larson** is a Corporate Fellow in the Materials Science & Technology Division at Oak Ridge National Laboratory (ORNL). He was Group Leader for X-Ray Diffraction in the Condensed Matter Sciences and Solid State Divisions at ORNL from 1973-2006 and Section Head from 1990-2003. His current research interests are (1) the structural dynamics of atomic displacement cascades on time-scales from sub-picoseconds to milliseconds, (2) the development and use of submicron-resolution 3D x-ray microscopy for fundamental investigations of materials microstructure and evolution on mesoscopic length scales, and (3) microsecond-resolution time-resolved x-ray studies of pulsed-laser deposition film growth. Larson was a recipient of the 1974 Sidhu Award by the Pittsburgh Diffraction Society and he received the 1985 Bertram Warren Diffraction Physics Award by the American Crystallographic Association for nanosecond-resolution synchrotron x-ray measurements of pulsed-laser melting in Si. He joined Oak Ridge National Laboratory in 1969 after receiving a PhD in Physics from the University of Missouri, Columbia, MO. Larson can be reached by phone at 865-574-5506 and by e-mail at [larsonbc@ornl.gov](mailto:larsonbc@ornl.gov).

